1. Record Nr. UNISA996386907303316

Autore	Bathurst Elizabeth <d. 1691.>
Titolo	Truth's vindication, or, A gentle stroke to wipe off the foul aspersions, false accusations, and misrepresentations cast upon the people of God called Quakers, both with respect to their principle and their way of proselyting people over to them [[electronic resource]] : also An epistle to such of the Friends of Christ that have lately been convinced of the truth as it is in Jesus
Pubbl/distr/stampa	[London, : s.n.], 1679
Descrizione fisica	[16], 104, [2] p
Soggetti	Society of Friends - Doctrines
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Dedication signed: Elizabeth Bathurst. First edition. Place of publication from Wing. Errata: p. [1] at end. Reproduction of original in Huntington Library.
Sommario/riassunto	eebo-0113

2. Record Nr. UNINA9910646364503321

Autore	Sassari
Titolo	Codice degli statuti della Repubblica di Sassari / edito e illustrato dal Cav. D. Pasquale Tola
Pubbl/distr/stampa	Cagliari, : Tip. A. Timon, 1850
Descrizione fisica	XXIII, 273 p., 3 c. di tav. : facs., ill. ; 30 cm
Disciplina	348.45931
Locazione	FGBC
Collocazione	V Z 35
Lingua di pubblicazione	Italiano
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	C. di tav. disegnate da Cosimo Tola Serra.

3. Record Nr. UNINA9911007368603321

Titolo	Handbook of silicon wafer cleaning technology / / edited by Karen A. Reinhardt, Werner Kern
Pubbl/distr/stampa	Norwich, NY, : William Andrew, c2008
ISBN	1-282-76970-7 0-08-094746-8 9786612769702 1-282-00282-1 9786612002823 0-8155-1773-4
Edizione	[2nd ed.]
Descrizione fisica	1 online resource (749 p.)
Collana	Materials science & process technology series
Altri autori (Persone)	ReinhardtKaren A KernWerner <1925->
Disciplina	621.3815/2
Soggetti	Silicon-on-insulator technology
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia

Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references and index.
Nota di contenuto	Front Cover; Handbook of Silicon Wafer Cleaning Technology; Copyright Page; Contents; Foreword; Preface to the Second Edition; Preface to First Edition; PART I: INTRODUCTION AND OVERVIEW; Chapter 1. Overview and Evolution of Silicon Wafer Cleaning Technology; 1.1 Introduction; 1.2 Importance of Clean and Conditioned Wafer Surfaces; 1.3 Overview of Wafer Contamination Aspects; 1.4 Overview of Wafer Cleaning and Surface Conditioning Technology; 1.5 Evolution of Wafer Cleaning Science and Technology; 1.6 Summary and Conclusion; References Chapter 2. Overview of Wafer Contamination and Defectivity2.1 Wafer Contamination; 2.2 Behavior and Impact of Contamination; 2.3 Sources of Defects and Contamination; References; PART II: WET CHEMICAL PROCESS; Chapter 3. Particle Deposition and Adhesion; 3.1 Introduction to Particle Deposition and Adhesion; 3.2 Particle Transport, Deposition, and Adhesion; 3.3 Particle Adhesion; 3.4 Particle Removal; 3.5 Summary; References; Chapter 4. Aqueous Cleaning and Surface Conditioning Processes; 4.1 Overview of Aqueous Cleaning, Rinsing, and Drying Applications and Techniques 4.2 Common Chemistries and Their Applications4.3 Process Variables Affecting Cleaning; 4.4. Rinsing and Drying; 4.5 Aqueous Cleaning Equipment; 4.6 Current and Future Challenges; 4.7 Summary; Acknowledgments; References; PART III: DRY CLEANING PROCESSES; Chapter 5. Gas-phase Wafer Cleaning Technology; 5.1 Introduction and Overview of Gas-Phase and Vapor-Phase Cleaning and Surface Conditioning; 5.2 Chemistry and Mechanisms; 5.3 Removal of Silicon Oxides with HF Vapor; 5.4 O3 and UV/O3 for Organic Removal, Resist Stripping, and Surface Oxidation; 5.5 UV/Cl2 for Metallic Contamination Removal 5.6 Applications for Gas-Phase Cleaning5.7 Process Equipment; 5.8 Integrated Process Equipment; 5.9 Summary; Acknowledgments; References; Chapter 6. Plasma Stripping, Cleaning, and Surface Conditioning; 6.1 Introduction to Plasma Stripping and Cleaning; 6.2 Applications of Plasma Stripping, Cleaning, and Surface Conditioning; 6.3 Mechanisms of Plasma Stripping, Cleaning, and Surface Conditioning; 6.4 Plasma Stripping, Cleaning, and Surface Conditioning Equipment; 6.5 Plasma Diagnostics; 6.6 Plasma Damage; 6.7 Conclusions; Acknowledgments; References Chapter 7. Cryogenic Aerosols and Supercritical Fluid Cleaning7.1 Cryogenic and Supercritical Cleaning as Emerging Technologies; 7.2 Introduction to Cryogenic Aerosols; 7.3 Introduction to Supercritical and Densified Fluid Cleaning; 7.4 Summary; Acknowledgments; References; PART IV: ANALYTICAL AND CONTROL ASPECTS; Chapter 8. Detection and Measurement of Particulate Contaminants; 8.1 Measurements of Particle and Defects; 8.2 Defect and Particle Measurements on Wafers; 8.3 Particle Measurement in Liquid Chemicals; 8.4 Particle Measurement in Vacuum, Gas, and Air; Acknowledgements; References Chapter 9. Surface Chemical Composition and Morphology
Sommario/riassunto	The second Edition of the Handbook of Silicon Wafer Cleaning Technology is intended to provide knowledge of wet, plasma, and other surface conditioning techniques used to manufacture integrated circuits. The integration of the clean processes into the device manufacturing flow will be presented with respect to other manufacturing steps such as thermal, implant, etching, and photolithography processes. The Handbook discusses both wet and

	plasma-based cleaning technologies that are used for removing contamination, particles, residue, and photoresist from wafer surfaces. Both the process and t

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Record Nr.	UNINA9910968876903321
Autore	Chui C. K.
Titolo	Kalman Filtering : with Real-Time Applications / / by Charles K. Chui, Guanrong Chen
Pubbl/distr/stampa	Berlin, Heidelberg : , : Springer Berlin Heidelberg : , : Imprint : Springer, , 1999
ISBN	3-662-03859-5
Edizione	[3rd ed. 1999.]
Descrizione fisica	1 online resource (XIV, 230 p.)
Collana	Springer Series in Information Sciences ; ; 17
Disciplina	629.8/312
Soggetti	Mathematical physics Econometrics Engineering mathematics Engineering - Data processing Telecommunication Artificial intelligence Mathematical Methods in Physics Theoretical, Mathematical and Computational Physics Quantitative Economics Mathematical and Computational Engineering Applications Communications Engineering, Networks Artificial Intelligence
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Bibliographic Level Mode of Issuance: Monograph
Nota di bibliografia	Includes bibliographical references and index.
Nota di contenuto	1. Preliminaries -- 2. Kalman Filter: An Elementary Approach -- 3. Orthogonal Projection and Kalman Filter -- 4. Correlated System and Measurement Noise Processes -- 5. Colored Noise -- 6. Limiting Kalman Filter -- 7. Sequential and Square-Root Algorithms -- 8. Extended Kalman Filter and System Identification -- 9. Decoupling of

Filtering Equations -- 10. Kalman Filtering for Interval Systems -- 11. Wavelet Kalman Filtering -- 12. Notes -- References -- Answers and Hints to Exercises.

Sommario/riassunto

Kalman Filtering with Real-Time Applications presents a thorough discussion of the mathematical theory and computational schemes of Kalman filtering. The filtering algorithms are derived via different approaches, including a direct method consisting of a series of elementary steps, and an indirect method based on innovation projection. Other topics include Kalman filtering for systems with correlated noise or colored noise, limiting Kalman filtering for time-invariant systems, extended Kalman filtering for nonlinear systems, interval Kalman filtering for uncertain systems, and wavelet Kalman filtering for multiresolution analysis of random signals. The last two topics are new additions to this third edition. Most filtering algorithms are illustrated by using simplified radar tracking examples. The style of the book is informal, and the mathematics is elementary but rigorous. The text is self-contained, suitable for self-study, and accessible to all readers with a minimum knowledge of linear algebra, probability theory, and system engineering.